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U.S. PATENT DOCUMENTS

Examiner Initials	Document Number	Issue Date	Name	Class	Sub Class	Filing Date If Appropriate
gw	5,674,355	10/1997	Cohen et al.	156	652,1	

FOREIGN PATENT DOCUMENTS

	Document Number	Publication Date	Country	Class	Sub Class	Translation Yes or No

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

gw	Treichel, H. et al., "Low dielectric constant materials for interlayer dielectric (Invited paper)", <i>Microelectronic Engineering</i> , 40 (1998), 1-19.
an	Murarka, S.P., "Low dielectric constant materials for interlayer dielectric applications", 400 <i>Solid State Technology</i> , 39 (1996) March, No. 3, Tulsa, OK, US.
pa	Wu, P.K., "XPS Study of Buried Metal/Polymer and Polymer/Metal Interface", <i>Mat. Res. Soc. Symp. Proc.</i> Vol. 385 (1995), pp. 79-90.
pa	Clark, D.T. et al., "Surface Modification by Plasma Techniques. I. The Interactions of a Hydrogen Plasma with Fluoropolymer Surfaces", <i>Journal of Polymer Science: Part A: Polymer Chemistry</i> , Vol. 25, 2643-64 (1987).
gw	Supplementary European Search Report, EP 99 91 8319, dated July 1, 2003.

Examiner <i>GW</i>	Date Considered <i>11/17/03</i>
*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	
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